

WHAT IS CLAIMED IS:

1 1. A device for providing environmental stability and mechanical
2 integrity in space, the device comprising:
3 a substrate;
4 a first silicon oxynitride layer on the substrate, the first silicon oxynitride layer
5 having a tensile stress;
6 a second silicon oxynitride layer on the first silicon oxynitride layer, the
7 second silicon oxynitride layer having a compressive stress.

1 2. The device of claim 1 is free from delamination and cracking of the
2 first silicon oxynitride layer and free from delamination and cracking of the second silicon
3 oxynitride layer after at least 60 hours under a first UV radiation in a first vacuum condition.

1 3. The device of claim 2 wherein the first UV radiation has a first UV
2 intensity equal to a second UV intensity of a second UV radiation received by a spacecraft in
3 space.

1 4. The device of claim 3 wherein the first vacuum condition has a first
2 vacuum pressure ranging from 1×10^{-6} torr to 1×10^{-3} torr.

1 5. The device of claim 1 is free from delamination and cracking of the
2 first silicon oxynitride layer and free from delamination and cracking of the second silicon
3 oxynitride layer after at least 3000 hours under a third UV radiation and a first electron and
4 proton bombardment in a second vacuum condition.

1 6. The device of claim 5 wherein the first electron and proton
2 bombardment has a first electron and proton intensity equal to a second electron and proton
3 intensity received by a spacecraft in space.

1 7. The device of claim 6 wherein the third UV radiation has a third UV
2 intensity equal to a fourth UV intensity of a fourth UV radiation received by the spacecraft in
3 space.

1 8. The device of claim 7, wherein the second vacuum condition has a
2 second vacuum pressure ranging from 1×10^{-12} torr to 1×10^{-7} torr.

1 9. The device of claim 1 wherein the tensile stress ranges from 0.01 MPa
2 to 1 MPa.

1 10. The device of claim 9 wherein the compressive stress ranges from 10
2 MPa to 100 MPa.

1 11. The device of claim 1 wherein the substrate comprises at least one
2 selected from a group consisting of polymer, ceramic, carbon composite, Kapton, black
3 Kapton, aluminum, aluminum alloy, silver, gold, platinum, titanium.

1 12. The device of claim 1 wherein the first silicon oxynitride layer
2 comprises SiO_xN_y , x ranging from 0 to 2, y ranging from 0 to $\frac{4}{3}$.

1 13. The device of claim 12 wherein the second silicon oxynitride layer
2 comprises SiO_xN_y , x ranging from 0 to 2, y ranging from 0 to $\frac{4}{3}$.

1 14. A device for providing environmental stability and mechanical
2 integrity in space, the device comprising:

3 a substrate;

4 a first coating layer on the substrate, the first coating layer having a tensile
5 stress;

6 a second coating layer on the first coating layer, the second coating layer
7 having a compressive stress;

8 wherein

9 the first coating layer is free from delamination and cracking and the second
10 coating layer is free from delamination and cracking after at least 60 hours under a first UV
11 radiation in a first vacuum condition, the first UV radiation having a first UV intensity equal
12 to a second UV intensity of a second UV radiation received by a spacecraft in space, the first
13 vacuum condition has a first vacuum pressure ranging from 1×10^{-6} torr to 1×10^{-3} torr.

1 15. A device having environmental stability and mechanical stability in
2 space, the device comprising:

3 a substrate;

4 a first coating layer on the substrate, the first coating layer having a tensile
5 stress;

a second coating layer on the first coating layer, the second coating layer having a compressive stress;
wherein the first coating layer is free from delamination and cracking and the second coating layer is free from delamination and cracking after at least 3000 hours under a first UV radiation and a first electron and proton bombardment in a first vacuum condition, the first electron and proton bombardment having a first electron and proton intensity equal to a second electron and proton intensity of a second electron and proton bombardment received by a spacecraft in space, the first UV radiation having a second UV intensity of a second UV radiation received by the spacecraft in space; the second vacuum condition having a second vacuum pressure ranging from 1×10^{-12} torr to 1×10^{-7} torr.

16. A device for providing environmental stability and mechanical integrity in space, the device comprising:

a substrate;
a silicon oxynitride coating layer on the substrate, the silicon oxynitride coating layer having a changing stress, the changing stress being compressive on a top surface of the silicon oxynitride coating layer and tensile on a bottom surface of the silicon oxynitride coating layer.

17. The device of claim 16, wherein the substrate comprises at least one selected from a group consisting of polymer, ceramic, carbon composite, Kapton, black Kapton, aluminum, aluminum alloy, silver, gold, platinum, titanium.

18. The device of claim 17, wherein the substrate comprises a reflective layer, the reflective layer reflecting solar radiation.

19. The device of claim 17 wherein the substrate comprises at least one selected from a group consisting of silver, aluminum, gold, platinum, and titanium.

20. The device of claim 16 wherein the silicon oxynitride coating layer comprises at least a first coating sub-layer and a second coating sub-layer, the first coating sub-layer on the second coating sub-layer, the first coating sub-layer having the compressive stress, the second coating sub-layer having the tensile stress.

21. The device of claim 20 wherein the first coating sub-layer has a first thickness ranging from 5 microns to 35 microns.

1 22. The device of claim 21 wherein the second coating sub-layer has a
2 second thickness ranging from 0.5 micron to 5 microns.

1 23. The device of claim 22 wherein the first thickness equals 19.5 microns.

1 24. The device of claim 23 wherein the second thickness equals 2.5
2 microns.

1 25. The method for making a protection device, the method comprising: ✓
2 depositing a first silicon oxynitride layer on a substrate using a first plasma
3 enhanced chemical vapor deposition process;
4 depositing a second silicon oxynitride layer on the first silicon oxynitride layer
5 with a second plasma enhanced chemical vapor deposition process;
6 wherein the first plasma enhanced chemical vapor deposition process having a
7 first power and a first pressure, the second plasma enhanced chemical vapor deposition
8 process having a second power and a second pressure, the second power higher than the first
9 power, the second pressure higher than the first pressure.

1 26. The method of claim 25 wherein the substrate comprises one selected
2 from a group consisting of polymer, ceramic, carbon composite, Kapton, black Kapton,
3 aluminum, aluminum alloy, silver, gold, platinum, titanium.

1 27. The method of claim 26 wherein the first power ranges from 25 W to
2 250 W, the first pressure ranges from 100 mTorr to 2000 mTorr.

1 28. The method of claim 27 wherein the second power ranges from 250 W
2 to 500 W, the second pressure ranges from 1000 mTorr to 2000 mTorr.

1 29. The method of claim 28 wherein the first power equals 150 watts, the
2 first pressure equals 1200 mTorr.

1 30. The method of claim 29 wherein the second power equals 325 watts,
2 the second pressure equals 1600 mTorr.

1 31. An optical solar reflector for providing environmental stability and ✓
2 mechanical integrity in space, the reflector comprising:
3 a substrate;

- 4 a reflection layer;
- 5 a first silicon oxynitride layer on the reflection layer, the first silicon
- 6 oxynitride layer having a tensile stress;
- 7 a second silicon oxynitride layer on the first silicon oxynitride layer, the
- 8 second silicon oxynitride layer having a compressive stress.